



## 66 -- Ultra High Vacuum Ga Ion Column

- [Synopsis](#) - Posted on Aug 10, 2005

### General Information

Document Type: Modification to a Previous Presolicitation Notice  
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### Contracting Office Address

Department of the Navy, Office of Naval Research, Naval Research Laboratory, 4555 Overlook Ave.  
S.W., Washington, DC, 20375

### Description

The combined synopsis/solicitation previously issued for the procurement of the following: Contract Line Item Number (CLIN) 0001, An Ultra High Vacuum (UHV) Ga Ion Column for Scanning Auger Microscope and Secondary Ion Mass Spectroscopy (SIMS); SubCLIN 0001AA UHV Ion Column, 1 EA; SubCLIN 0001AB Installation, 1 LO; SubCLIN 0001AC Training, 1 LO; CLIN 0002 Operation and Maintenance Manuals, 1 LO. is hereby modified as follows: REPLACE: The focused (less than 50 nm) ion beam position on the sample must be able to be controlled in X and Y using two external voltage sources. 1 mm deflection of the ion beam must be possible in both X and Y directions using external voltage sources. The purpose of controlling the beam position is for ion beam lithography, and thus the beam deflection must be suitable for a range of lithography write field areas from 1 mm maximum deflection to less than 0.1 micron area; WITH: The focused (less than 50 nm) ion beam position on

the sample must be able to be controlled in X and Y using two external voltage sources. 1 mm deflection of the ion beam must be possible in both X and Y directions using external voltage sources. The purpose of controlling the beam position is for ion beam lithography, and thus the beam deflection must be suitable for a range of lithography write field areas from 500 microns maximum deflection to less than 0.1 micron area.

### **Point of Contact**

Lisa Fleming, Contract Specialist, Phone 202-767-3739, Fax 202-767-6197, Email  
lisa.fleming@nrl.navy.mil

### **Place of Performance**

Address: Naval Research Laboratory Washington DC  
Postal Code: 20375-5326  
Country: USA

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